



THE UNITED STATES PATENT AND TRADEMARK OFFICE

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In re application of:
Vincent S. CHANG, et al.

Serial No.: 10/758,317

Group Art Unit: 1765

Filed: January 15, 2004

Examiner: Duy Vu Nguyen Deo

**For: HIGH TEMPERATURE HYDROGEN
ANNEALING OF A GATE INSULATOR
TO INCREASE ETCHING SELECTIVITY
BETWEEN CONDUCTIVE GATE
STRUCTURE AND GATE INSULATOR
LAYER**

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT AFTER FINAL

Sir:

In response to the Final Office Action mailed February 15, 2006, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 8 of this paper.